

**IN THE SPECIFICATION**

Please amend the specification as follows:

[0015] The RF sources 104, 106 are independent, frequency-tuned RF generators. The RF sources 104, 106 may be configured to provide RF power to the chamber 102 in any desired frequency to control characteristics of the plasma. Both frequencies may be selected to control the same plasma characteristic or, alternatively, to control different plasma characteristics. For example, in one embodiment, one of the RF sources 104, 106 is capable of providing high frequency power to excite the plasma and dissociate ions in the plasma and the other one of the RF sources 104, ~~[[406]]~~ 106 is capable of providing low frequency power to modulate the plasma sheath voltage. For example, in one embodiment, the source 104 may be generally capable of generating a frequency in the range of from about 12.8MHz to about 14.3MHz at up to 5000W of either continuous or pulsed power. The source 106 may be generally capable of generating a frequency in the range of from about 1.8MHz to about 2.2MHz at up to 5000W of either continuous or pulsed power. It is contemplated that other frequencies may be employed.